Graphene Nanoribbon Field-Effect Transistor Fabrication using Block Copolymer Lamellar

<u>박승규</u>, 박범진, 이규성, 현 승, 김진곤[†] 포항공과대학교 (jkkim@postech.ac.kr[†])

Precise spatial control over the electrical properties of thin films is the key capability enabling the production of modern integrated circuitry. So we have to find another building block as insulator and combine these two building blocks into one circuit. On the other hand, uniform edge of graphene is important factor for electronic devices. Recently, some groups reported that graphene nanoribbon field–effect transistor using top–down method like lithography. However, this graphene nanoribbon field–effect transistor have not uniform edges of graphene due to using lithography. Here, we report that one step growth of graphene/amorphous carbon(G/AC) hetero–structures from solid source as polystyrene–b–polymethylmetacrylate (PS–b–PMMA) perpendicular lamellar via UV irradiation. This bottom–up approach also overcomes problem of graphene edges due to getting uniform edges.